DiagSupport™ dC Succinyl PEG-Polystyrene Resin, 90 µm, 0.15-0.22 mmol/g

Cat.No: SPS-RA23-469

DESCRIPTION

Description	PEG-polystyrene resins consist of a low crosslinked polystyrene matrix on which polyethylene glycol (PEG or POE) is grafted. The PEG spacer is attached to the matrix via an ethyl ether group which increases stability towards acid treatment and minimizes PEG-leaching. The resins show modified physico chemical properties which are highly dominated by the PEG moiety. These graft copolymers are pressure stable and can be used in batch processes as well as under continuous flow conditions. The PEG spacer is in the range of MW 3000 Da. These resins are designed for automated large scale oligonucleotide synthesis, which are recommended for the synthesis of up to 25 mer oligos.

APPLICATION

Application Notes	For the synthesis of up to 25 mer oligos.

PRODUCT INFORMATION

Particle Size	90 µm
Functional Group	dC
Capacity	0.15-0.22 mmol/g

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